

Please replace claim 1 with the following:

10 1 A magnetic thin film comprising:
an iron nitride thin film having a nitrogen martensite α'
phase with α (002) surface formed on a substrate using an
opposed-target DC sputtering method by means of reactive
sputtering with N_2 gas wherein said iron nitride thin film
15 produced using an N_2 gas flow rate ratio of 25% permitting
diffraction rays from a γ' phase to be observed, said α' phase
having diffraction rays observed from only said α (002) surface.

Please replace claim 2 with the following:

2. A magnetic thin film comprising:

iron (α - Fe) thin films and iron nitride thin films
alternately deposited on a substrate by means of an opposed-
target DC sputtering method, said iron nitride thin films having
5 a nitrogen martensite α phase with α (002) surface, said α'
phase having diffraction rays observed only from said α (002)
surface wherein a coercive force of said iron nitride thin films
is substantially 1.0 Gauss.

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